**Simple manual for Pt Sputter**

28/Jun./2018 Toshihiro Hayakawa

**Preparation**

1. Make sure that power switch at lower right is OFF.



1. Open upper cover and take off glass chamber.



※Don’t contact seal area of glass chamber with anything.

Take care that glass chamber rolls over.

1. Set sample on sample stage.
2. Incline sample stage slightly.

(※In case of sample with a lot of asperity）

1. Set glass chamber and close upper cover.

**Film Formation by Pt Sputter**

1. Switch on power switch and emission starts automatically.
2. Wait until pressure in chamber down under 20Pa.
3. Set “coating time” and ”sputtering” current”

・Make sure that[Mode](a) is “Auto”.

・Push [DISPRA](b) and set “coating time” by pushing (c).

・Select “sputtering current” from (d).

* Decide ”coating time” and “sputtering current” from following graph arbitrarily .

1. Turn on tab for rotation of sample stage.
2. Conduct Pt sputtering.

Push [START](f) and start sputtering.

　　※Emission and sputtering start automatically as following step.

(For about 15 minutes)

1. After sputtering, turn off tab for rotation of stage.
2. Switch off power switch.
3. Wait for becoming atmosphere pressure.
4. Open upper cover and take off glass chamber. Take back tilt of sample stage and take out sample.

**Finish**

1. Clean off glass chamber with ethanol and Kim Wipes.
2. Make sure that there`re no dust.
3. Set glass chamber and upper cover.